

IN THE CLAIMS:

Please CANCEL claims 1-10 without prejudice to or disclaimer of the recited subject matter.

Please ADD new claims 11-16, as follows. For the Examiner's convenience, all claims currently pending in this application have been reproduced below:

1-10. (Canceled)

11. (New) An exposure apparatus for exposing a substrate to a pattern of a reticle, said apparatus comprising:

a stage to hold one of the substrate and the reticle;

a motor to drive said stage, said motor having a coil and a jacket to cover said coil; and

a first adjustment system to adjust temperature of said motor, said first adjustment system having a flow path of pure water through said jacket, and an impurity removing unit, arranged upstream with respect to said jacket in the flow path, to remove an impurity in the pure water.

12. (New) An apparatus according to claim 11, further comprising:

a chamber in which the substrate is exposed to the pattern of the reticle and into which a gas is supplied through a filter; and

a second adjustment system which has a flow path of a coolant to adjust temperature of the gas.

13. (New) An apparatus according to claim 11, further comprising:

a projection optical system to expose the substrate to the pattern of the reticle; and

a third adjustment system which has a flow path of a coolant to adjust temperature of said projection optical system.

14. (New) An apparatus according to claim 11, wherein the flow path of said first adjustment system is a circulation path.

15. (New) An apparatus according to claim 11, wherein said first adjustment system comprises a detection unit to detect a temperature of the pure water, an adjustment unit to adjust a temperature of the pure water, and a controller to control said adjustment unit based on a temperature detected by said detection unit.

16. (New) A method of manufacturing a device, said method comprising steps of:

exposing a substrate to a pattern of a reticle using an exposure apparatus as defined in claim 11;

developing the exposed substrate; and

processing the developed substrate to manufacture the device.